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Processing and Characterization of Materials Using Ion Beams

Editors: Lynn E. Rehn, Joe Greene and Fred A. Smidt

Index

[More information](#)

755

Author Index

- Al-Jumaily, G.A., 61, 475, 483
 Allen, Charles W., 297
 Amaral, L., 315
 Anderson, Alfredo C., 67
 Andreadis, T.D., 151, 175, 201
 Arnold, G.W., 713

 Baca, A.G., 249
 Bai, Xinde, 479
 Balanzat, E., 357
 Baldo, Pete, 213
 Baliga, B.J., 731
 Barnett, S.A., 689
 Basheer, R.A., 737
 Bassel, R.H., 151
 Battaglia, A., 563
 Baxi, H., 231
 Becker, M.F., 551
 Behar, M., 315
 Berger, S., 647
 Berti, M., 569
 Birtcher, R.C., 303
 Børgesen, P., 207, 219, 261
 Borisenko, V.E., 653, 659
 Bouffard, S., 357
 Boulding, A., 17
 Bowman, Jr., Robert C., 629
 Boyer, L.L., 483
 Bradley, R.M., 269
 Bube, Richard H., 701
 Buchal, Ch., 719
 Burke, R., 291
 Burton, L.C., 677

 Calcagno, L., 581
 Campisano, S.U., 581
 CaO, D.X., 587
 Carnera, A., 563
 Carosella, C.A., 79, 501
 Catania, M., 581
 Cerofolini, G.F., 181
 Chang, Albert L., 433
 Chason, Eric, 35
 Chen, G-S., 195
 Chen, Heming, 479
 Chen, Q.M., 225
 Cheng, C.C., 445
 Cheng, Y.-T., 189
 Choi, C.-H., 689
 Chu, W.K., 375, 707
 Cirlin, E.-H., 189
 Clayton, Clive, 463
 Clemens, B.M., 189
 Cole, E.D., 677
 Cornett, Kenneth D., 495

 Cortesi, E., 623
 Culbertson, R.J., 321
 Cuomo, Jerome J., 23
 Custer, J.S., 545

 Dai, Mingjiang, 479
 Daly, James, 463
 Dauplaise, H.M., 61
 Davari, B., 635
 Davis, G., 617
 de Beurs, H., 403
 De Hosson, J. Th. M., 403
 Delafond, J., 91
 Demchenko, A.I., 653
 Dieleman, Jan, 3
 Dietrich, H.-P., 507
 Dietrich, Harry B., 665
 Dillard, J.G., 677
 Dillich, S.A., 427
 Dodson, Brian W., 137
 Donley, M.S., 469
 Donovan, E.P., 55, 79, 501
 Dow, A.A., 189
 Drigo, A.V., 569

 Echeverria, A., 231
 El-Ghor, M.K., 593
 Epp, J., 677
 Erck, R.A., 445
 Eridon, James M., 175, 201, 665
 Eto, K., 513

 Fahrenbruch, Alan L., 701
 Fair, Richard B., 611
 Fan, Y.D., 225
 Farkas, D., 195
 Feng, G.F., 671
 Fenske, G.R., 445
 Ferla, G., 563, 581
 Follstaedt, D.M., 309, 389
 Forchel, A., 749
 Foti, G., 581
 Franzen, W., 321
 Fujihana, Takanobu, 415
 Fujii, K., 743

 Ganin, E., 635
 Gasparotto, A., 563
 Germann, R., 749
 Gfeller, F., 507
 Ghibaudo, G., 599
 Ghosh, P.K., 725
 Gibson, Ursula J., 495
 Gilmore, C.M., 163

Cambridge University Press

978-1-107-41087-9 - Materials Research Society Symposium Proceedings: Volume 128:

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Editors: Lynn E. Rehn, Joe Greene and Fred A. Smidt

Index

[More information](#)

756

- Grabowski, K.S., 279
 Greenwald, Anton C., 109, 463
 Gresko, Thomas, 665
 Guillermet, M., 291
 Günter, P., 719

 Haeri, A., 163
 Harame, D., 635
 Harper, J.M.E., 269
 Hart, R.R., 575
 Haynes, T.E., 47
 Heim, D.J., 285
 Herbots, N., 641
 Hirvonen, J.-P., 85, 439, 451, 457
 Hirvonen, James K., 85, 109, 439
 Hoffman, D., 641
 Holesinger, T.G., 285
 Holland, O.W., 47, 593
 Hong, Shin-Nam, 611
 Hörcher, G., 749
 Horn, K.M., 35
 Horne, C.R., 617
 Hörnström, S.E., 269
 Hren, John J., 611
 Huang, J.S., 327
 Huang, L.J., 225
 Hubler, G.K., 55, 79, 151

 Inoue, K., 381
 Irmscher, R., 719
 Isa, Saliman A., 725
 Ishibashi, K., 381
 Iskanderova, Z.A., 169
 Ito, K., 513
 Ivanov, A.I., 653
 Iwaki, Masaya, 415, 421

 Jacobson, D.C., 243, 533
 Jaggi, Narendra K., 109
 Janssen, K.T.F., 557
 Jaouen, H., 599
 Jaulin, M., 91
 Jeon, Young-Jin, 551
 Jervis, T.R., 451, 457
 Jiankun, Zhou, 73
 Johnson, H.H., 207, 219
 Jones, K.S., 249, 617
 Jousset, J.C., 357
 Jun, Li, 237

 Kaim, R.E., 557
 Kalitzova, Maria G., 683
 Kant, R.A., 55, 279, 427, 433
 Karasinski, J., 17
 Kasi, S.R., 101
 Kataoka, I., 513
 Kawata, Y., 381
 Kenik, E.A., 333

 Kinomura, A., 743
 Kiuchi, M., 743
 Knapp, J.A., 389
 Knudsen, John F., 629
 Koike, J., 339, 345
 Komem, Y., 647
 Kornreich, P.G., 725

 La Ferla, A., 563
 Lakin, K.M., 125, 285
 LaPlanche, G., 91
 Lau, W.M., 695
 Leiderman, R. Yu., 169
 Levenson, Leonard L., 131
 Lewis, N., 731
 Li, H-D., 225
 Li, Jian, 255, 297
 Li, Wangpei, 479
 Lichtenwalner, D.J., 67
 Lifshitz, Y., 101
 Lilienfeld, D.A., 207, 219, 261
 Liu, A.S., 303
 Liu, B.X., 225
 Liu, Joyce C., 297
 Lopez-Otero, Adolfo, 701
 Lotti, R., 569
 Lowder, L.J., 321
 Lulli, G., 569

 Ma, D., 641
 Machida, Kazumichi, 525
 Maeyama, Yoshitaka, 525
 Martin, J.A., 457
 Massalski, T.B., 231
 Matsuo, T., 743
 Mayer, J.W., 255, 297
 Mazzone, A.M., 157
 McDevitt, N.T., 469
 McNally, J.J., 483
 McNeil, J.R., 483
 Meda, L., 181
 Meng, W.J., 345
 Merli, P.G., 569
 Meroth, John, 463
 Meshii, M., 339
 Mizutani, Tatsumi, 605
 Mooney, T.A., 61, 475
 Moser, A., 507
 Moss, Steven C., 629
 Mueller, G.P., 151
 Murray, P.T., 469
 Musket, R.G., 327
 Myers, Edward R., 611
 Myers, S.M., 309

 Nagakubo, M., 29
 Namavar, F., 623
 Namba, S., 381, 743
 Naoe, M., 29

Cambridge University Press

978-1-107-41087-9 - Materials Research Society Symposium Proceedings: Volume 128:

Processing and Characterization of Materials Using Ion Beams

Editors: Lynn E. Rehn, Joe Greene and Fred A. Smidt

Index

[More information](#)

757

- Nastasi, Michael, 333, 351, 451, 457
 Nishimatsu, Shigeru, 605
 Noguchi, Kazuhiko, 525

 Ohwaki, Takeshi, 41
 Okabe, Yoshio, 415
 Okamoto, P.R., 339, 345
 Oliver, Richard, 463
 Oliver, W.C., 457
 Oyoshi, Keiji, 519
 Ozturk, Mehmet, 611

 Parikh, N.R., 375
 Park, B., 243
 Park, Won Woo, 551
 Parker, G., 439
 Parkin, Don M., 351
 Pashov, N.K., 683
 Pearce, J.D., 575
 Pearton, S.J., 249
 Pennycook, S.J., 47
 Petkie, R., 17
 Pharr, G.M., 457
 Picraux, S.T., 35
 Pimbert-Michaux, S., 91
 Ping, Cai Wei, 237
 Poate, J.M., 243, 533, 545
 Pope, L.E., 389
 Priolo, F., 243, 533, 563
 Pyatkova, T.M., 659

 Qadri, S.B., 279
 Qu, Yi, 409

 Rabalais, J.W., 101
 Radjabov, T.D., 169
 Ramos, Stella M.M., 315
 Rangaswamy, M., 195
 Rehn, Lynn E., 213, 297, 339, 345
 Reicher, D.W., 483
 Rimini, E., 563, 581
 Rizzo, H.F., 231
 Rosen, D.J., 175
 Rosen, M., 151, 175, 201
 Rossi, M., 683
 Roy, Ronnen A., 17, 23
 Rubin, Leonard M., 641
 Rubio, J.D., 575
 Rudeck, P.J., 269
 Rudman, D.A., 67
 Ruggles, Gary A., 611
 Run, Wu, 237

 Sai-Halasz, G.A., 635
 Said, J., 599
 Sampath, W.S., 409
 Sandhu, G.S., 707
 Saris, F.W., 557

 Sartwell, B.D., 427
 Sasaki, Jun, 421
 Sasaki, Shigeo, 525
 Satou, M., 743
 Scheuer, Udo, 213
 Schreutelkamp, R.J., 557
 Scilla, G., 635
 Sen, S., 677
 Shanks, H.R., 125, 285
 Sharps, Paul, 701
 Shenai, K., 731
 Shichang, Zou, 73
 Short, K.T., 249
 Siochi, A., 677
 Sioshansi, Piran, 463, 623
 Sjoreen, T.P., 593
 Smajkiewicz, A., 475
 Smith, Duane D., 629
 Smith, G.A., 731
 Sood, D.K., 587
 Spaepen, F., 243
 Spinella, C., 563, 581
 Sprague, J.A., 163, 427
 Spurgeon, W.A., 61
 Stoemenos, I., 599
 Suzuki, N., 381
 Swansiger, W.A., 309
 Swanson, M.L., 375, 707
 Swartzlander, Amy B., 131

 Taga, Yasunori, 41
 Tagami, Takashi, 519
 Takagi, Toshinori, 131
 Takai, M., 381, 743
 Tanaka, Shuhei, 519
 Taylor, Anthony, 495
 Tesmer, J.R., 451
 Tetreault, Thomas G., 439
 Thompson, Michael O., 533, 545
 Thompson, Phillip E., 665
 Tokarev, V.V., 653, 659
 Toulemonde, M., 357
 Tsao, J.Y., 35
 Tukfatullin, F.K., 169
 Turner, D.E., 125

 Ueda, Ryuzi, 525
 Usui, Hiroaki, 131

 Vallier, L., 291
 Van Vechten, D., 55, 79, 501
 Vardiman, R.G., 369
 Vaseashta, A., 677
 Vasquez, A., 315
 Venables, D., 617
 Vettiger, P., 507
 Vijay, R.P., 575
 Vitali, G., 683
 Voisin, E., 291

Cambridge University Press

978-1-107-41087-9 - Materials Research Society Symposium Proceedings: Volume 128:

Processing and Characterization of Materials Using Ion Beams

Editors: Lynn E. Rehn, Joe Greene and Fred A. Smidt

Index

[More information](#)

758

Volpones, C., 181

Wall, M.A., 327

Walser, Rodger M., 551

Wang, S.Q., 255

Webb, D.J., 507

Wei, Huang, 73

Wei, Ronghua, 409

Wei, Tian, 237

Weimann, G., 749

Westendorp, J.F.M., 557

White, C.W., 593

Wilbur, P.J., 409

Williams, F.L., 483

Williamson, D.L., 409

Wistrom, R.E., 207, 219

Wortman, Jimmie J., 611

Wu, C.S., 249

Xianghuai, Liu, 73

Yamada, I., 513

Yamada, Isao, 113, 131

Yamamoto, T., 29

Yee, Dennis S., 17, 23

Youshan, Chen, 73

Yu, N., 375

Yunogami, Takashi, 605

Zallen, R., 671, 677

Zarovsky, D.I., 653

Zaumseil, P., 599

Zawislak, F.C., 315

Zhang, Z.H., 375

Zhihong, Zheng, 73

Zinkle, S.J., 363

Zocco, T.G., 451, 457

Zuhr, R.A., 47

Zuyao, Zhou, 73

Cambridge University Press

978-1-107-41087-9 - Materials Research Society Symposium Proceedings: Volume 128:

Processing and Characterization of Materials Using Ion Beams

Editors: Lynn E. Rehn, Joe Greene and Fred A. Smidt

Index

[More information](#)

759

Subject Index

- adhesion, 439, 445, 475
- alloy
 - AgCu, 231
 - AgFe, 231
 - AgZn, 175
 - Al-Cu, 269
 - Co-Ti, 219
 - Cr-Ni, 237
 - Cr-Ni-Cr, 237
 - CuTi, 339
 - CuW, 231
 - Fe-Cr, 421
 - Fe-Cu, 225
 - Fe-Mo, 225
 - Fe-Ti, 207, 213, 219
 - Fe-Ti-C, 451
 - MoCu, 231
 - NiAl, 333
 - Ni₂Al₃, 333
 - Ni-Ti, 207, 219
 - PdTi, 219
 - PuTa, 231
 - PuV, 231
 - Ti-Al, 219
 - Ti₆Al₄V, 463
 - Ti-Cu, 219
 - Ti-W, 647
 - Zr₃Al, 345
- aluminum oxynitride, 61
- amorphization, 181, 333, 339, 345, 351, 629, 635
- amorphous, 79, 213, 231, 237, 243, 327, 351, 389, 501, 533, 545, 557, 563, 587, 599, 647
- angle of incidence, 269, 321
- annealing, 501, 587, 677
- anodic oxidation, 237, 479
- Auger electron spectroscopy, 73, 327, 427, 653, 659
- bonding, 463
- carbide
 - SiC, 91, 369
 - TiC, 91, 369
- carbonitrides, 315
- cascade, 151, 157, 189, 195
- cavity, 363, 525
- cluster beam, 113, 125, 131, 285
- coating, 169
- colloids, 363
- columnar structure, 29
- composition, 269, 427
- compressive state, 403
- computer simulation, 137, 151, 157, 163, 175
- contacts, 647
- corrosion, 463, 507
- crystallization, 369, 545, 557, 563, 569, 719
- damage, 181, 581, 593, 605, 671, 677, 689, 707, 749
- damage depth, 749
- defects, 175, 201, 357, 689
- densification, 151
- deposition, 17, 41, 85, 91, 101, 109, 131, 169, 475, 513, 563, 725, 743
- deuterium, 309
- diamond, 101, 707
- diamond-like, 109
- diffusion, 131, 163, 189, 201, 213, 243, 533, 587, 653, 731
- dilatational strain, 345
- dislocations, 363, 557
- disorder, 333, 575
- dissolution, 315
- dopant, 617, 701, 707, 731, 737
- dose rate, 243
- electrical activation, 599, 611, 635, 665, 701, 707
- electrical conductivity, 737
- electroless plating, 525
- electrolytes, 479
- electron irradiation, 333, 339, 345, 351
- electron microscopy
 - analytical, 333
 - cross-sectional TEM, 445, 593, 635
 - high resolution, 683
 - Nomarski, 285
 - RHEED, 35, 285
 - SEM, 285, 433, 641
 - TEM, 47, 73, 91, 231, 237, 309, 333, 363, 369, 427, 433, 445, 569, 599, 623, 683, 731
- electronic excitation, 357
- element
 - a-Si, 551, 647

Cambridge University Press

978-1-107-41087-9 - Materials Research Society Symposium Proceedings: Volume 128:

Processing and Characterization of Materials Using Ion Beams

Editors: Lynn E. Rehn, Joe Greene and Fred A. Smidt

Index

[More information](#)

760

- Ag, 125, 131, 175, 255, 475, 545
 Al, 61, 131, 479, 647
 Ar, 409, 575
 As, 569, 581, 599
 Au, 297, 309, 533, 743
 B, 109, 375, 421, 653, 707
 Ba, 261
 Be, 671
 Bi, 261
 C, 85, 109, 327, 389
 Co, 47
 Cr, 237, 255, 421, 445
 Cu, 3, 261, 309, 545
 Fe, 29, 47, 237, 315, 321, 415
 Ga, 617
 Ge, 35, 125, 151, 285, 581, 593, 611, 683
 H, 85, 219, 345, 439, 713
 He, 363
 Li, 713
 Mo, 743
 N, 61, 315, 375, 409, 415, 421, 463, 519, 695
 N₂, 55
 Nb, 269, 327
 Ni, 47, 279, 303, 513
 O, 85, 309, 363, 375, 463, 563, 593, 623
 P, 519, 551, 557, 617
 S, 665
 Si, 3, 41, 61, 113, 157, 243, 279, 291, 533, 545, 551, 557, 563, 569, 575, 581, 593, 611, 617, 623, 659, 665, 677, 689, 731, 743
 Ta, 269
 Ti, 47, 237, 255, 369, 389, 457
 W, 17
 Y, 261
 Zn, 175
 Zr, 255
 ellipsometry, 285
 embedded atom method, 175
 energy loss
 electronic, 357
 nuclear, 569
 enhanced diffusion, 213, 243
 epitaxial, 101, 279, 291, 545, 569, 587, 659, 689, 701
 etching
 ion-beam, 525, 749
 reactive ion, 731
 evaporation, 23
 Fermi level, 695
 film, 17, 29, 41, 55, 79, 445, 575
 focused ion beam, 743
 fractal, 189
 friction, 389, 421, 439, 451, 457, 463
 GeV ions, 357
 Gibbs phase rule, 327
 grain boundary, 261, 297
 grain growth, 297
 growth, 35, 163, 291, 533, 659
 hard film, 85, 439
 hardness, 79, 421, 439, 457, 463
 heat of mixing, 207, 231
 high-energy, 445, 665
 hopping conduction, 737
 hot implants, 581
 I-V characteristics, 647
 icosahedral, 225
 impingement ratio, 55, 79, 433
 implantation depth, 421
 impurity, 545, 551, 599
 index of refraction, 79, 501
 inert gas, 303
 interface structure, 445
 intermetallic, 231, 345
 ion-assisted deposition, 445, 483, 495
 ion-beam analysis
 channeling, 279, 375, 557, 575, 581, 593, 659
 elastic recoil detection, 713
 forward recoil spectroscopy, 85
 light element detection, 375
 microprobe, 381, 743
 nuclear reaction, 85, 309
 PIXE, 381
 quantitative, 375
 Rutherford backscattering, 47, 73, 255, 375, 381, 415, 479, 519, 557, 569, 575, 629, 641, 659, 743
 ion beam annealing, 575
 ion beam mixing, 195, 207, 213, 219, 225, 243, 249, 261, 451
 ion bombardment, 29, 55, 213, 269, 297, 409, 427
 ionization, 285
 junction, 611

Cambridge University Press

978-1-107-41087-9 - Materials Research Society Symposium Proceedings: Volume 128:

Processing and Characterization of Materials Using Ion Beams

Editors: Lynn E. Rehn, Joe Greene and Fred A. Smidt

Index

[More information](#)

761

- Knoop hardness, 415
- laser
 - evaporation, 469
 - interferometry, 551
 - melting, 457
 - mixing, 451
 - processing, 403
- lattice defects, 357
- lattice parameter, 303
- liquid-solid interface, 533
- low-energy, 137, 157, 189, 291, 445, 483, 611, 695
- magnetic, 29, 225, 357
- magneto-optic, 495
- maskless, 743
- mass spectrometer, 3, 125
- melting, 303
- metal film, 23, 113
- metal-semiconductor, 659
- metallization, 249, 641
- metastable solid solution, 327
- microhardness, 23
- microstructure, 23, 131, 269, 363, 369, 409, 427, 445
- microtopography, 525
- migration energy, 175, 201
- modeling, 137, 151, 157, 163, 169, 175, 181, 195
- molecular beam epitaxy, 35
- molecular dynamics, 137, 157
- molecular ions, 181, 695
- morphology, 237, 433
- Mossbauer, 315, 409
- multilayers, 219, 225, 243
- neutral beam, 605
- nitride
 - BN, 79, 85, 439, 469
 - FeN, 321
 - Fe₄N, 415
 - NbN, 67
 - SiN, 439, 501
 - Si₃N₄, 369
 - TiN, 55, 73, 427, 433, 439
- nucleation, 163
- optical
 - coatings, 507
 - materials, 483
 - properties, 61, 79, 501, 671, 707
 - waveguide, 719
- orientation, 269, 321
- oxide, 61, 731
 - Al₂O₃, 363, 495, 507, 587
 - CuO, 255
 - Fe₂O₃, 415
 - KNbO₃, 719
 - LiNbO₃, 713, 719
 - Li₂O, 513
 - SiO₂, 41, 513, 605, 623, 731
 - Y₃Fe₅O₁₂, 357
 - ZnO, 725
 - ZrO₂, 495
- oxygen precipitates, 617
- oxynitride, 519
- p-n junctions, 731
- passivation, 507
- permeability, 309
- phase stability, 333, 357
- phosphosilicate glass, 519
- photoconductive switches, 629
- photoconductivity, 707
- photoluminescence, 749
- pin-on-disk, 451, 463
- pitting corrosion, 495
- plasma
 - assisted epitaxy, 291
 - etching, 67, 731
- plastic lenses, 525
- point defect, 195, 345, 581, 599
- pole figure, 279
- polyacrylonitrile, 737
- porosity, 445
- precipitate, 303, 315, 333, 369
- precision molds, 525
- prostheses, 463
- protective overlayers, 495
- proton, 375
- quadrupole, 381
- quantum, 749
- quartz, 513
- radiation damage, 351, 683
- radiation-enhanced diffusion, 213
- radiation-induced
 - segregation, 333
- Raman, 629, 677
- range, 665
- rapid thermal annealing, 557, 641, 659, 677
- reactive
 - ion etching, 731
 - physical vapor deposition, 427
 - sputtering, 67
- refractive index, 713
- regrowth, 545, 551, 563, 617
- resistivity, 23, 47, 285
- roughening, 35

Cambridge University Press

978-1-107-41087-9 - Materials Research Society Symposium Proceedings: Volume 128:

Processing and Characterization of Materials Using Ion Beams

Editors: Lynn E. Rehn, Joe Greene and Fred A. Smidt

Index

[More information](#)

762

- scanning micro-reflectometer, 495
- Schottky barrier, 249, 695
- scratch, 475
- secondary ion, 41
- secondary ion mass spectrometry, 519, 665, 749
- segregation, 201, 333, 533, 545
- self annealing implantation, 569
- semiconductor
 - Al_2O_3 , 363, 495, 507, 587
 - CdTe , 701
 - GaAlAs , 749
 - GaAs , 249, 665, 671, 677, 683, 695, 749
 - Ge , 35, 125, 151, 285, 581, 593, 611, 683
 - InAs , 689
 - KNbO_3 , 719
 - LiNbO_3 , 713, 719
 - NiP , 525
 - Si , 3, 41, 61, 113, 157, 243, 279, 291, 533, 545, 551, 557, 563, 569, 575, 581, 593, 611, 617, 623, 659, 665, 677, 689, 731, 743
 - SiO_2 , 41, 513, 605, 623, 731
 - TiB_2 , 653
 - TiSi_2 , 641
 - WSi , 249
 - ZnO , 725
- semiconductor injection
 - lasers, 507
- shallow junction, 635, 641
- sheet resistance, 635, 641, 659, 725
- silica glass, 519
- silicide, 47, 249, 647, 653, 659
- silicon-on-insulator, 623
- silicon-on-sapphire, 629
- silicon oxynitride, 61
- SIMOX, 617, 623
- smoothing, 35
- solar cells, 701
- solid phase epitaxy, 551, 557, 563, 599
- solid-state reaction, 255
- sputtering, 29, 41, 67, 91, 109, 231, 269, 333, 483, 507, 513, 725
- steel, 91, 315, 389, 439, 451, 457
- sticking coefficient, 55
- stress, 17, 23, 507
- subplantation model, 101
- superadditivity, 181
- superconductor, 261, 351
- surface
 - morphology, 35, 131, 285, 695
 - processes, 3, 163
 - ripple, 269
 - structure, 457
- Talystep, 525
- tensile stress, 403
- texture, 17
- thermal spike, 157, 163, 189, 195, 261
- thin film, 41, 47, 61, 109, 131, 163, 269, 469, 575
- time-of-flight, 3, 125, 469
- topography, 269
- transient reflectivity, 563
- tribology, 91, 389, 403, 409, 415, 421, 427, 433, 439, 451, 463
- ultraviolet reflectivity, 671
- vacancy, 175, 219, 569, 581
- vacuum ultraviolet photons, 605
- Vickers hardness, 421
- void, 151
- waveguiding, 713
- wear, 389, 403, 409, 439, 457, 463
- x-ray
 - diffraction, 17, 73, 231, 243, 255, 279, 321, 415, 469, 599, 653, 659, 689
 - optics, 513
 - photoelectron spectroscopy, 415, 519, 677, 695